



PATENT
Attorney Docket No. 400113/ASAHIWA

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

HIROAKI SATOH

Application No. 09/271,447

Art Unit: 1762

Filed: March 18, 1999

Examiner: M. Cleveland

For: PROCESS FOR FORMING A PATTERN
OF FLUORESCENT SUBSTRATE AND
PLASMA DISPLAY PANEL

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PENDING CLAIMS AFTER AMENDMENTS
MADE IN RESPONSE TO OFFICE ACTION DATED DECEMBER 20, 2002

20. A process for forming a pattern of fluorescent substance into the cell of a fluorescent substance display substrate comprising providing inside the cell two separate layers which are (i) a resin composition (A) layer and (ii) a photosensitive resin composition (B) layer, exposing the layers to light, developing the exposed layers, and baking the developed layers; wherein the resin composition (A) layer consists essentially of an acrylic polymer (a) having a weight average molecular weight of 10000 to 300000 and an acid number of 80 to 250 mgKOH/g, a fluorescent substance (b), a compound containing at least one ethylenically unsaturated group (c) having a viscosity of 5-15000 mPa.sec at 20°C, and a polymerization inhibitor (d), and the resin composition (A) layer is disposed between the inside of the cell and the photosensitive resin composition (B) layer.

21. A process for forming a pattern of fluorescent substance into the cell of a fluorescent substance display substrate, wherein a resin composition (A) layer, consisting essentially of an acrylic polymer (a) having a weight average molecular weight of 10000 to 300000 and an acid number of 80 to 250 mgKOH/g, a fluorescent substance (b), a compound containing at least one ethylenically unsaturated group (c) having a viscosity of 5-15000 mPa.sec at 20°C, and a polymerization inhibitor (d), and a photosensitive resin composition (B) layer are formed inside the cell, and then they are exposed, developed and baked, wherein the photosensitive resin composition (B) layer is formed in the cell after the resin composition (A) layer is formed.

22. A process for forming a pattern of fluorescent substance into the cell of a fluorescent substance display substrate comprising providing inside the cell two separate layers which are (i) a resin composition (A) layer and (ii) a photosensitive resin composition (B) layer,

wherein the resin composition (A) layer, consisting essentially of an acrylic polymer (a) having a weight average molecular weight of 10000 to 300000 and an acid number of 80 to 250 mgKOH/g, a fluorescent substance (b), a compound containing at least one ethylenically unsaturated group (c) having a viscosity of 5-15000 mPa.sec at 20°C, and a polymerization inhibitor (d), and the photosensitive resin composition (B) layer are formed inside the cell, and then they are exposed, developed and baked, wherein the photosensitive resin composition (B) layer is formed in the cell after the resin composition (A) layer is formed.